



Method of Measuring Dishing
Jaime Poris
Application No: 09/578,798
Docket No. NAN040 US

1/4

FIG. 1A
(Conventional)

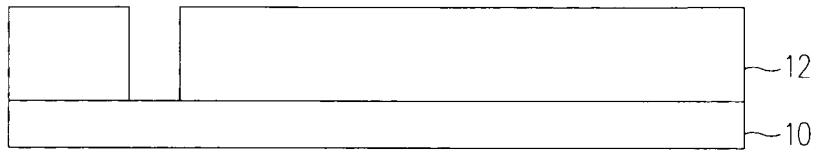


FIG. 1B
(Conventional)

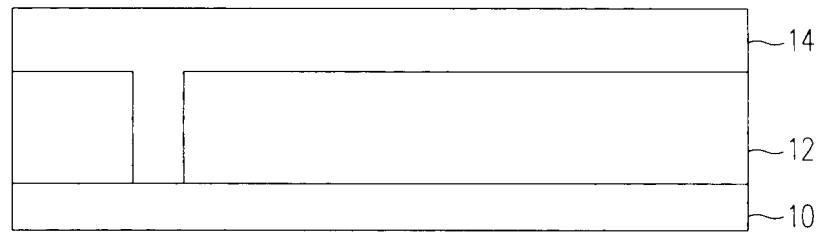


FIG. 1C
(Conventional)

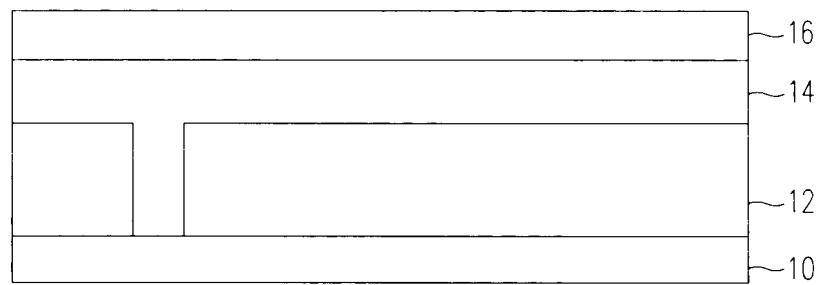


FIG. 1D
(Conventional)

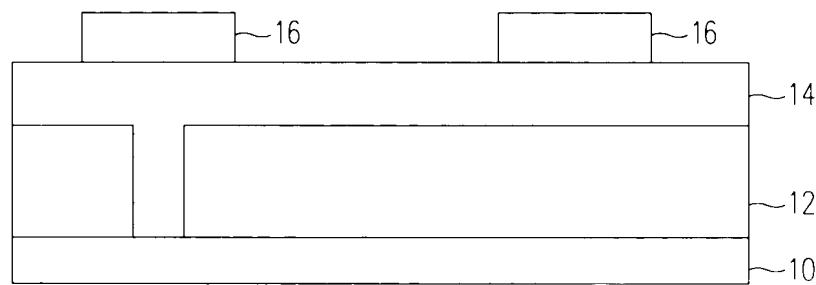
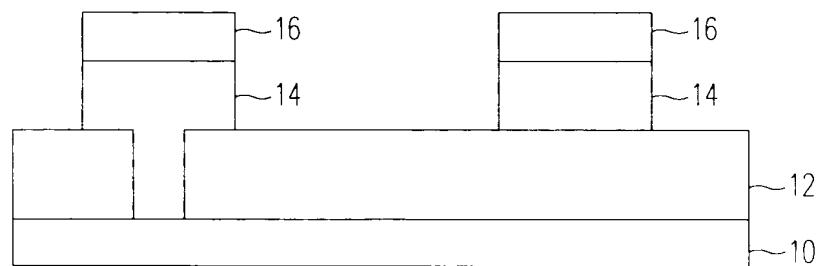


FIG. 1E
(Conventional)





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2/4

FIG. 1F
(Conventional)

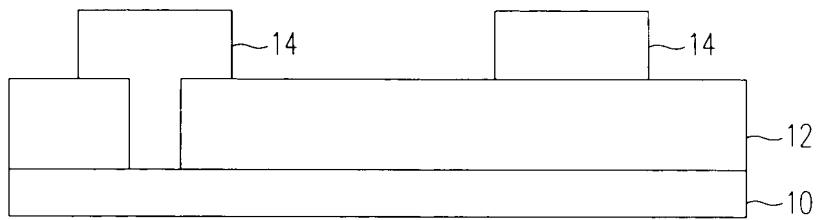


FIG. 1G
(Conventional)

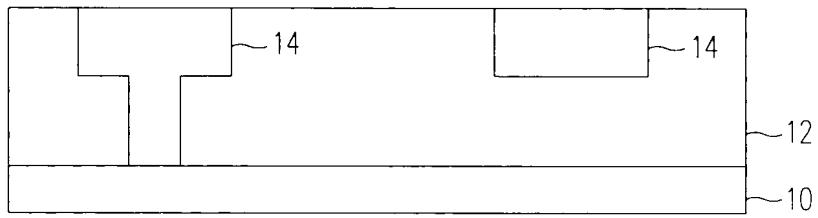


FIG. 2A
(Conventional)

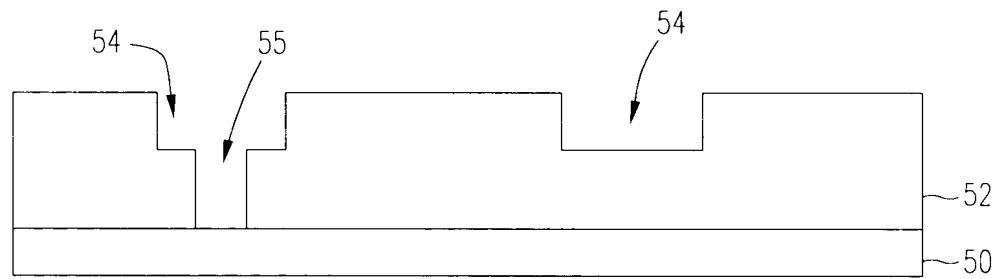


FIG. 2B
(Conventional)

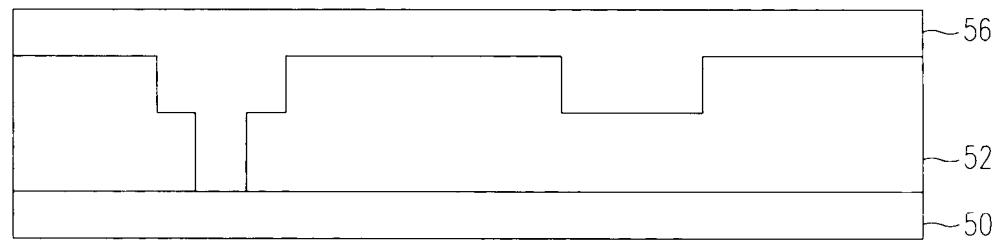
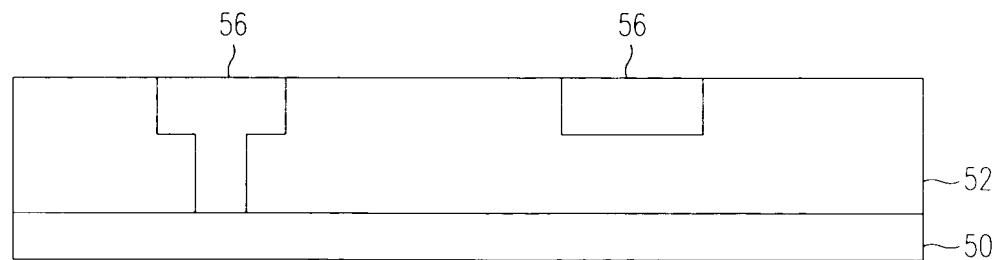


FIG. 2C
(Conventional)





Method of Measuring Dishing
Jaime Poris
Application No: 09/578,798
Docket No. NAN040 US

3/4

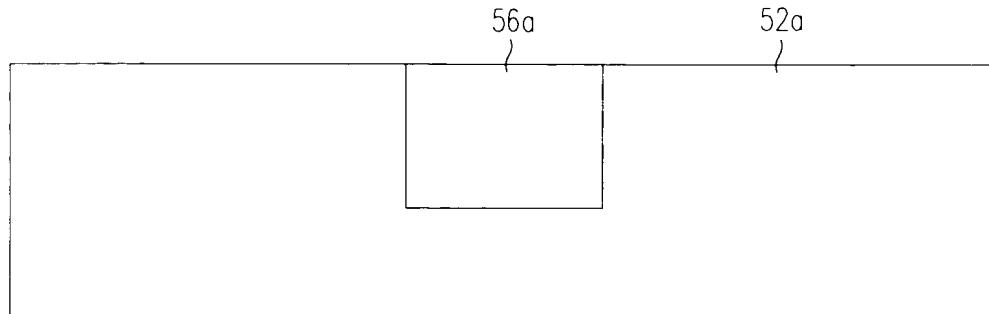


FIG. 3
(Conventional)

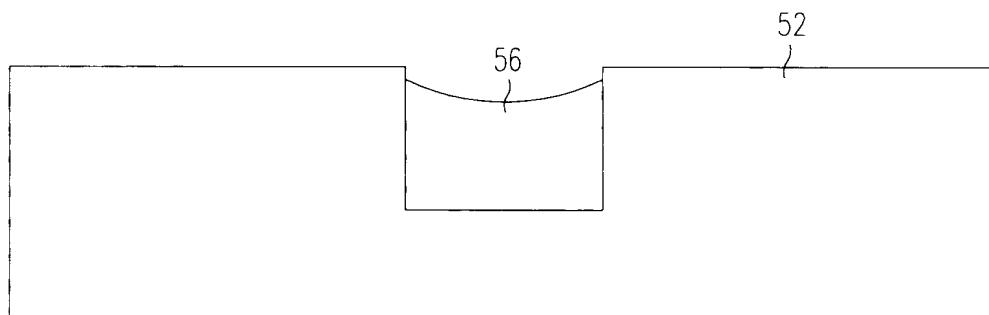


FIG. 4
(Conventional)

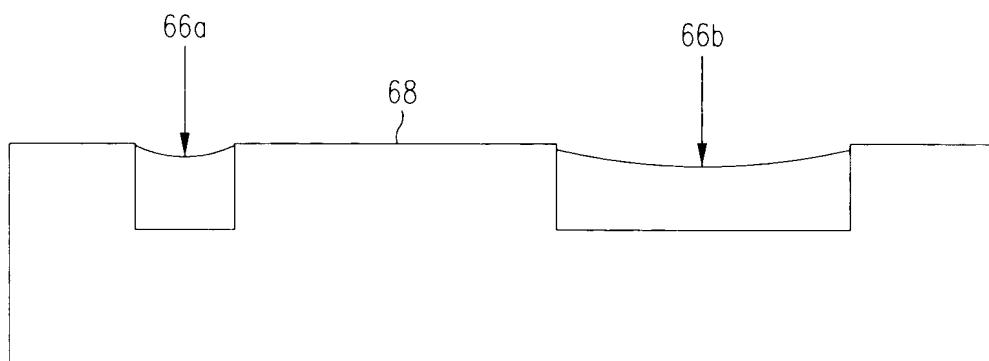


FIG. 5



Method of Measuring Dishing
Jaime Paris
Application No: 09/578,798
Docket No. NAN040 US

4/4

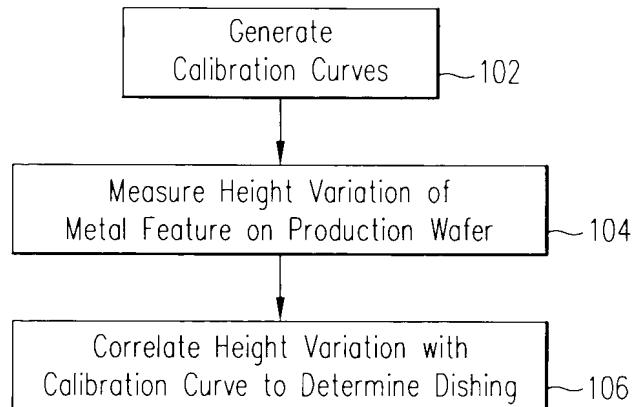


FIG. 6

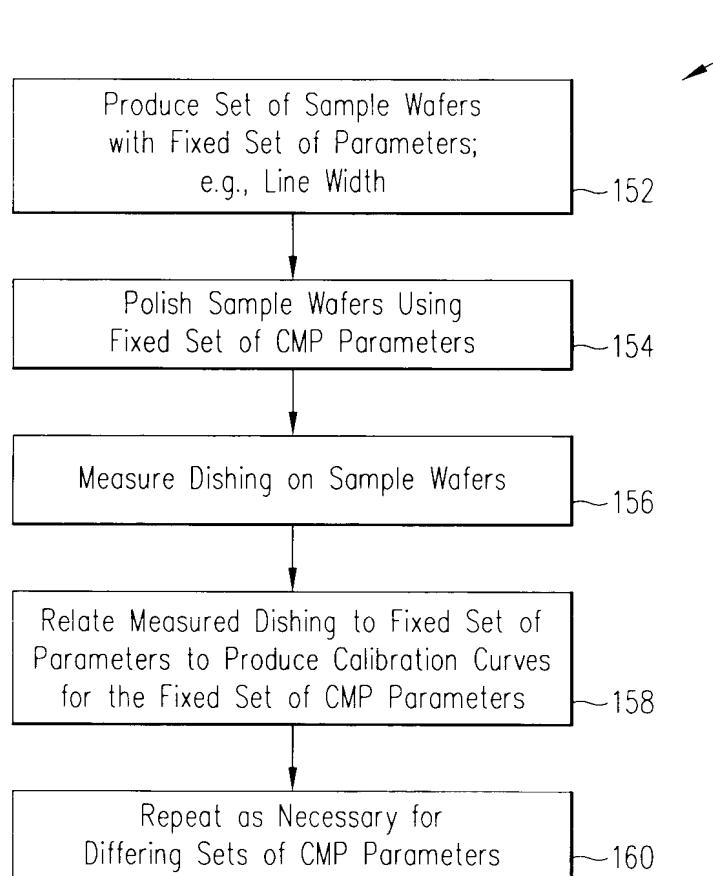
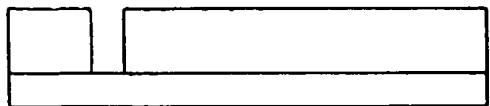
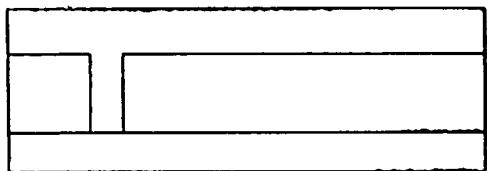


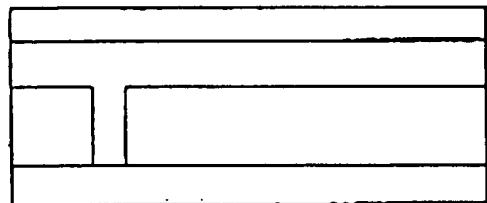
FIG. 7



PATTERNEDE AND ETCHED DIELECTRI



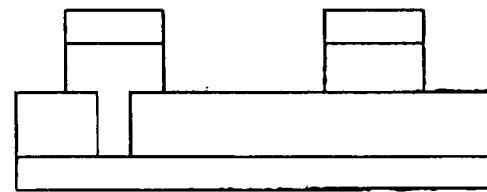
ALUMINUM DEPOSITION



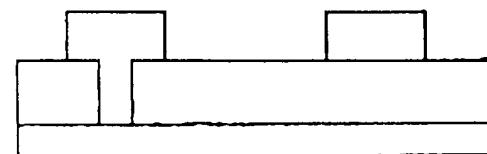
PHOTORESIST DEPOSITION



EXPOSURE AND DEVELOP



ALUMINUM ETCHING



PHOTORESIST REMOVAL

FIGURE 1

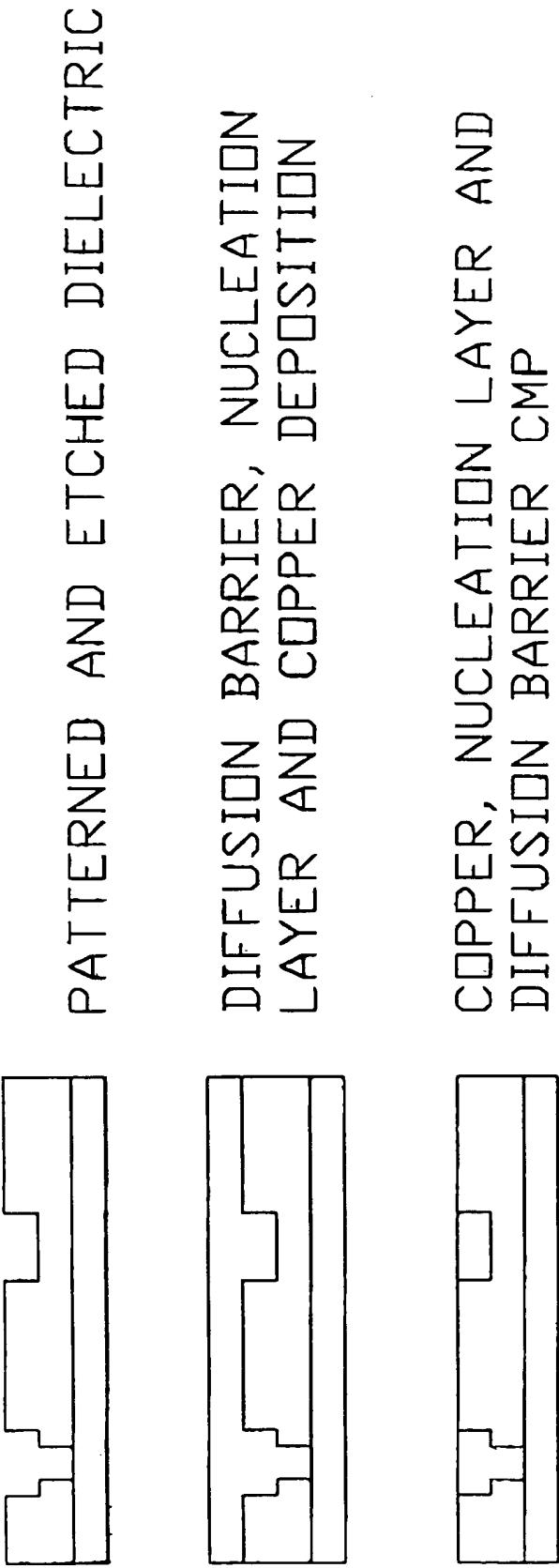


FIGURE 2

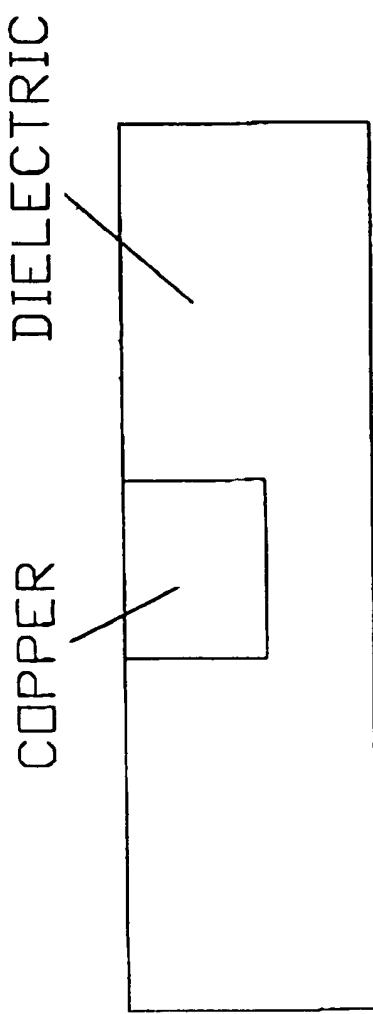


FIGURE 3

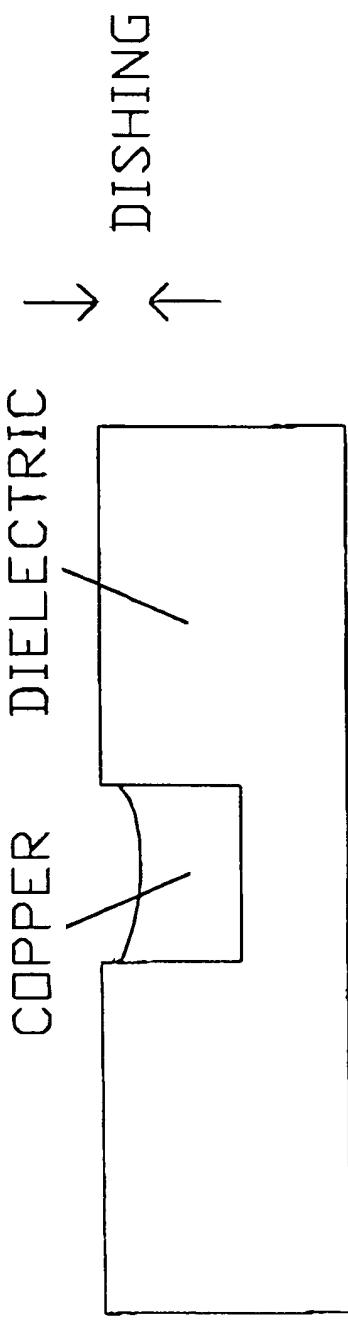


FIGURE 4



LARGE RADIUS
OF CURVATURE

SMALL
RADIUS OF
CURVATURE

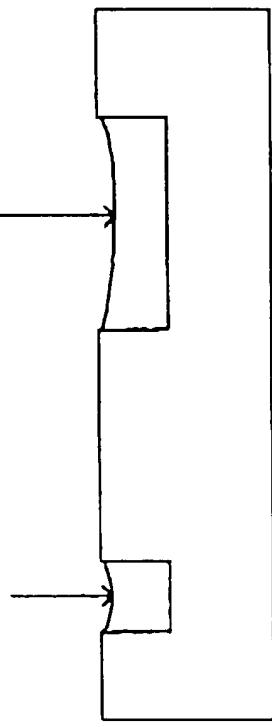


FIGURE 5